



INFORMATION
DISCLOSURE
STATEMENT BY APPLICANT

Sheet 1 of 1

Application Number: 09/638,075
 Filing Date: August 11, 2000
 First Named Inventor: Hiroji HANAWA, et al.
 Group Art Unit: 1753
 Examiner Name: Rodney McDonald
 Attorney Docket Number: 004609 M Y1

U. S. PATENT DOCUMENTS

Examiner Initials	Document No	Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date
<i>rm</i>	US-6,395,150 B1	05-28-2002	CAN CLEEMPUT ET AL.	204	192.37	04-01-1998
<i>rm</i>	US-6,413,321 B1	07-02-2002	KIM ET AL.	118	725	12-07-2000
<i>rm</i>	US 2003/0013260 A1	01-16-2003	GOSSMAN ET AL.	438	301	07-16-2001
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FOREIGN PATENT DOCUMENTS

Examiner Initials	Foreign Patent Document	Publication Date	Country	Name of Patentee or Applicant of Cited Document	Translation? (Yes/No/n/a)
<i>rm</i>	EP 1 158 071 A2	28.11.2001	EUROPE	APPLIED MATERIALS, INC.	N/A
<i>rm</i>	JP 07045542	14.02.1995	JAPAN	MATSUSHITA ELECTRIC IND CO LTD	N/A
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NON PATENT LITERATURE DOCUMENTS

<i>rm</i>	Hu, C.-K., et al., "A process for improved Al(cu) reactive ion etching", <u>Journal of Vacuum Science and Technology</u> , May 1, 1989, pp. 682-685, Vol. 7, No. 3, American Institute of Physics, New York, U.S.

Examiner's Signature:

Date Considered: 1/6/06

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.